



L'électronique de spin (spintronique) : une solution d'avenir pour un numérique frugale (?)

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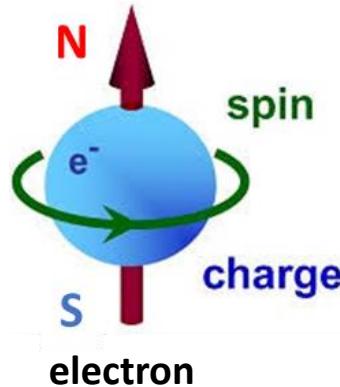
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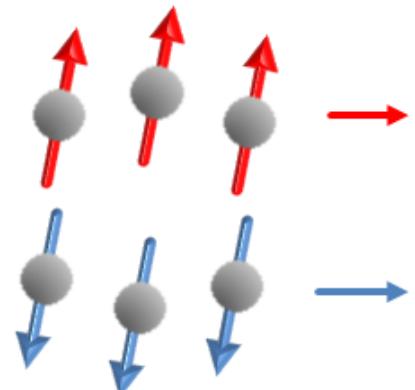
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- **La Spintronique et ses applications phares**
 - **Les challenges de la mémoire embarquée**
 - **Des solutions spintronique pour le numérique de demain**
 - **Conclusions**

Qu'est ce que la spin-elec-tronics?

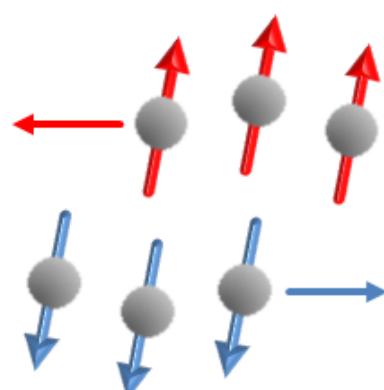
Spintronics – make use of **intrinsic quantum property of electrons (spin)** as additional degree of freedom for new electronics



Electrical current



Spin current



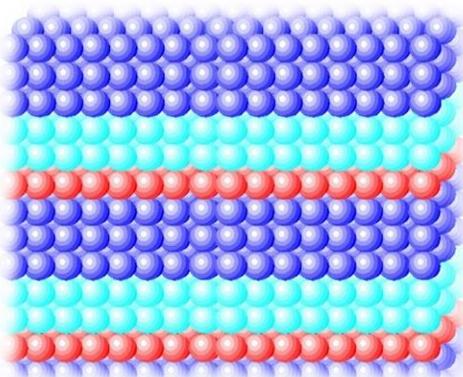
Ultralow power consumption (pJ - aJ)

$$E = R I^2 \Delta t$$

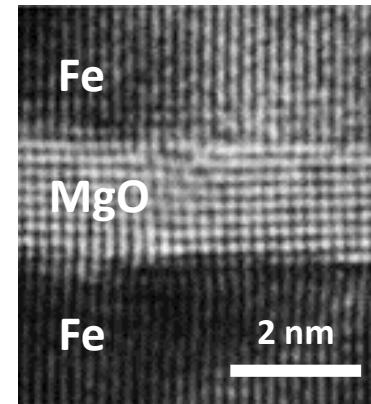
Ultrafast dynamics (ns - fs)

Materials engineering at nanoscale range

Magnetic multilayers

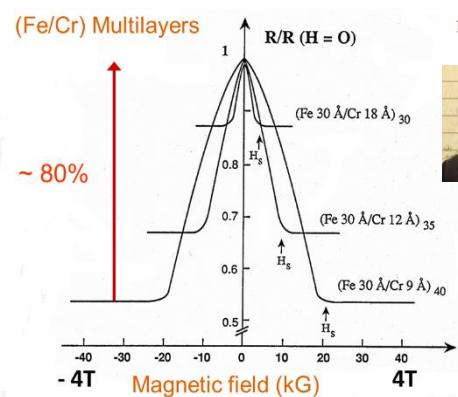


Cross-section image of a multilayer



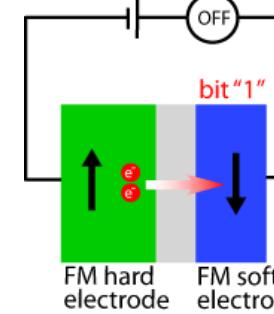
Combined to currents

Large magneto-resistance signals

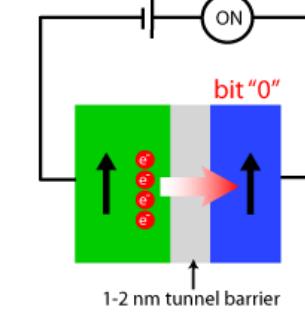


Gives sensor / memory device

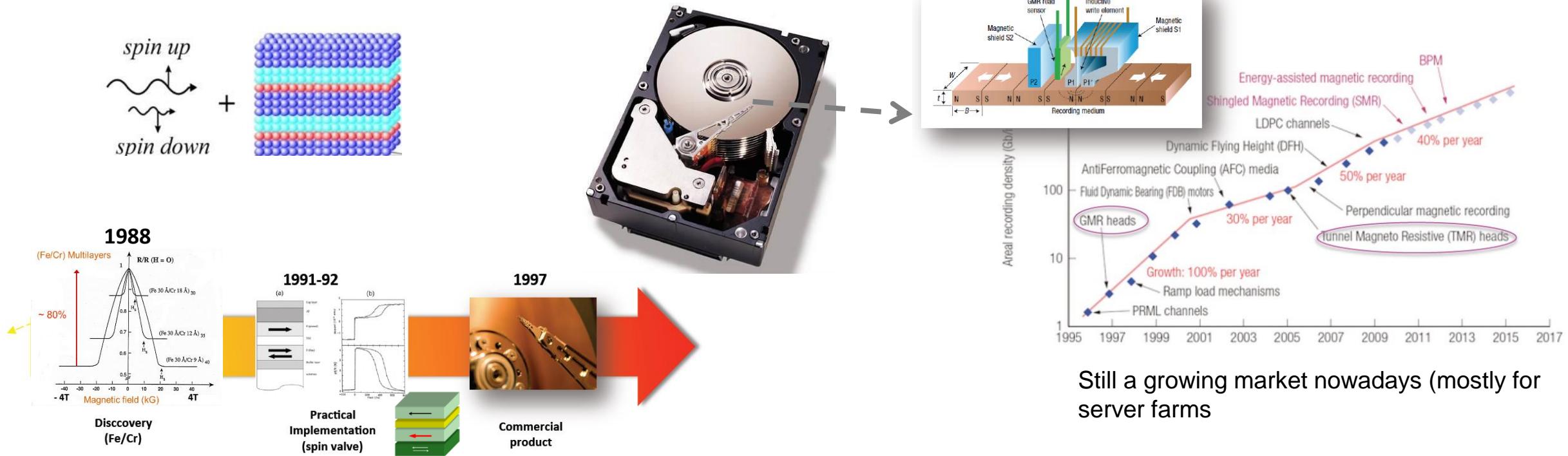
High resistance R_{AP}
antiparallel state



Low resistance R_P
parallel state

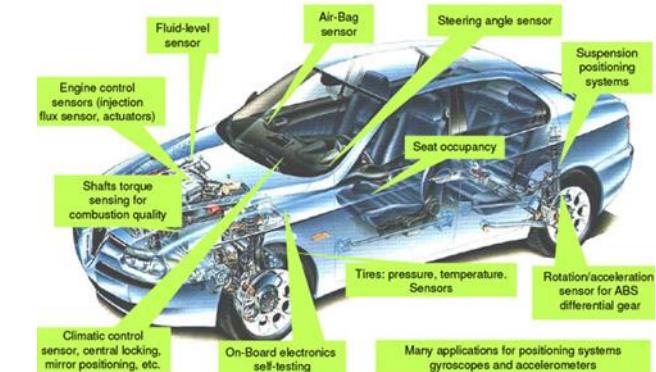


1st revolution : magnetic recording and sensors



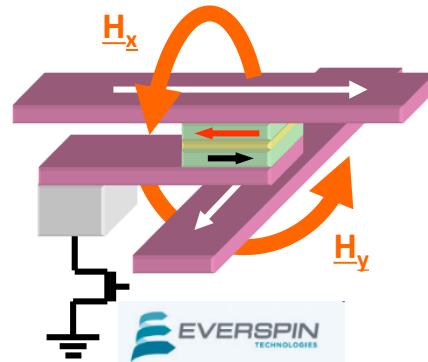
Still a growing market nowadays (mostly for server farms)

Direct impact on market with magnetic field sensors
Today in MEMS, minimally invasive surgery, Automotive sensors, Anti-skid system, speed control and navigation...

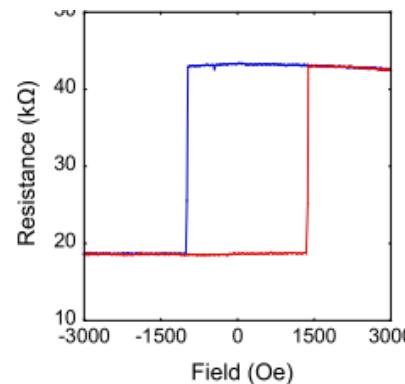


2nd ongoing revolution : MRAMs

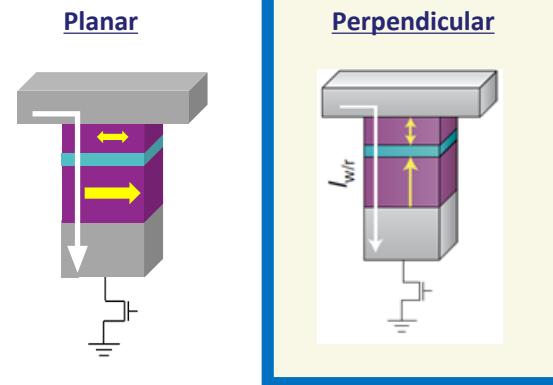
Field-driven MRAM



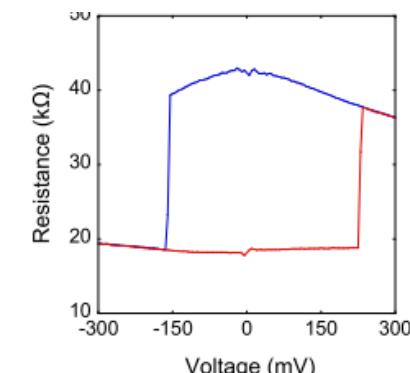
Toggle MRAM



Current-driven MRAM



Spin transfer torque (STT)

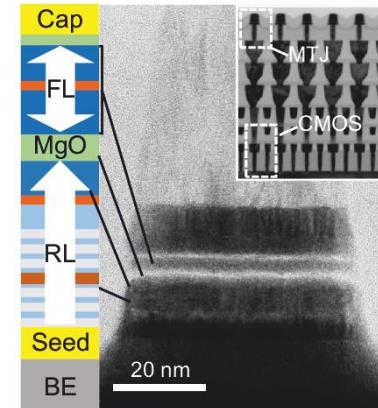


Brique de base: jonction tunnel magnétique (MTJ)

Lecture : TMR (tunnel magneto-resistance)(~ 200%)

Ecriture: STT → Convertir charge en spin via un matériau ferromagnétique + transférer un couple

→ STT-MRAM = Un contrôle toute électrique



Stockage: FL (>10y)

Stack MRAM moderne

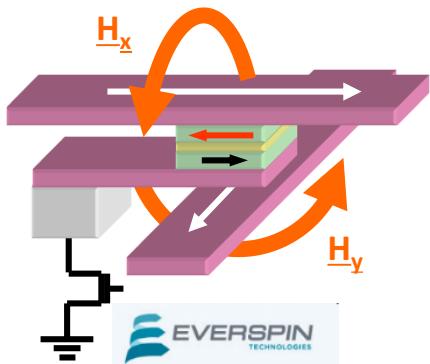
- 8 compounds
- sub-nm layers
- > 20 layers
- Supporte 400C

Mais des matériaux « critiques »: Ta, Pt, Ru, Co...
→ projet NEED pour minimiser/substituer ces matériaux

2nd ongoing revolution : MRAMs

Legacy

Field-driven MRAM

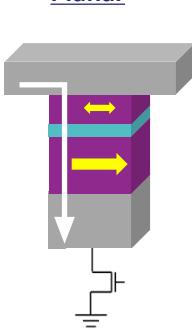


Toggle MRAM

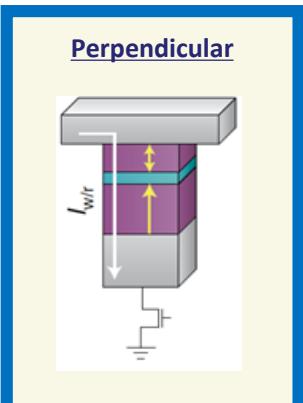
Maturity, production

Current-driven MRAM

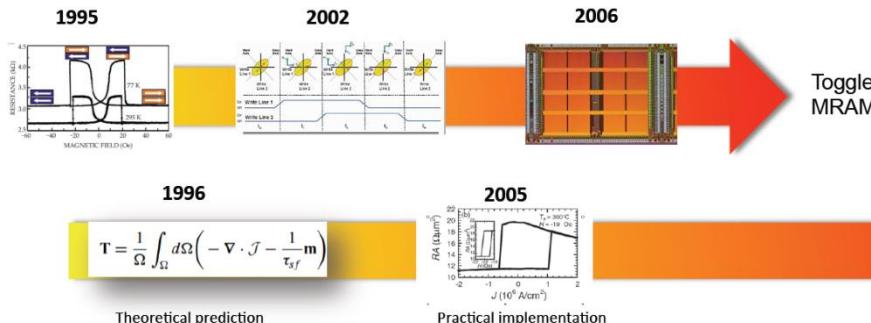
Planar



Perpendicular

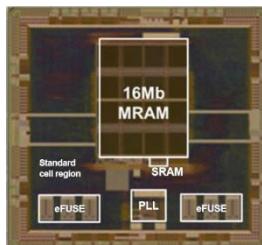


Spin transfer torque (STT)



But only for standalone

Since 2012, major actors of semiconductor-foundries, IDM, tool suppliers active for embedded MRAM



DIGITIMES

Samsung ready to mass produce MRAM chips using 28nm FD-SOI process

Tsing Lin, Taipei, Jessie Shun, DIGITIMES (Tuesday, 26 September 2017)

Samsung Foundry will soon be ready to enter mass production of magnetoresistive random-access memory (MRAM) chips built using 28nm fully depleted silicon-on-insulator (FD-SOI) process technology, according to Korea media reports.

Samsung is reportedly learning up with NXP and has completed the tape-out of its 28nm FD-SOI embedded MRAM, which will be first applied to NXP's new low-power i.MX series solution targeted at automotive, multimedia and display panel applications.

In related news, Synopsys announced recently its Design Platform has been fully certified for use on Samsung's 28nm FD-SOI process technology A-PDK and a comprehensive reference flow, compatible with Synopsys' Lynx Design System, containing scripts, design methodologies and best practices is now available.

tsmc

TSMC to start eMRAM production in 2018

June 08, 2017 - MRAM production

According to reports, Taiwan Semiconductor Manufacturing Company (TSMC) is aiming to start producing embedded MRAM chips in 2018 using a 22 nm process. This will be initial "risk production" to gauge market reception.

SAMSUNG

GLOBALFOUNDRIES

EVERSPIN TECHNOLOGIES

GF-EverSpin 2X nm eMRAM with superior data retention - VLSI Symposium

GLOBALFOUNDRIES and EverSpin continue to drive embedded MRAM (eMRAM) forward into the 22nm process node! Please see our technical paper presented this week at VLSI Symposium in Japan.

For the first time, we are unveiling eMRAM that can retain data through solder reflow at 260°C and 10+ years at 125°C, plus read/write with outstanding endurance at 125°C.

This is a major breakthrough from GLOBALFOUNDRIES and EverSpin that enables eMRAM to be used for general purpose MCU's and Automotive SOCs.

intel

Intel says its embedded 22nm MRAM is production ready

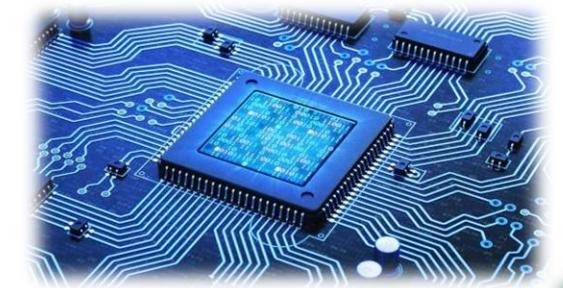
In October 2018 Intel unveiled that it is developing embedded MRAM, and that the company has successfully integrated embedded MRAM into its 22nm F+BI CMOS technology on full 300mm wafers.

MRAM-intro, 20 Feb. 2019.

MRAM: un stack, de multiples opportunities µelec

Spintronic & FD-SOI for Ultra-low power

Mobile applications, server clusters, HPC, beyond CMOS

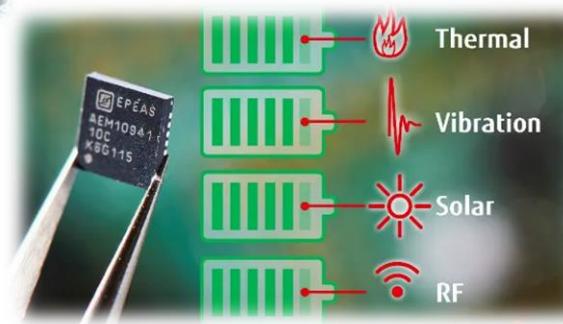


Spintronic Neural Networks
Artificial Intelligence

MIAI@GRENOBLE ALPES



Hardness to radiations-
Defense, nuclear & aerospace



IoT, 5G : RF devices, telecoms, wake-up receivers

Field / position / speed sensor - **automotive, IoT**

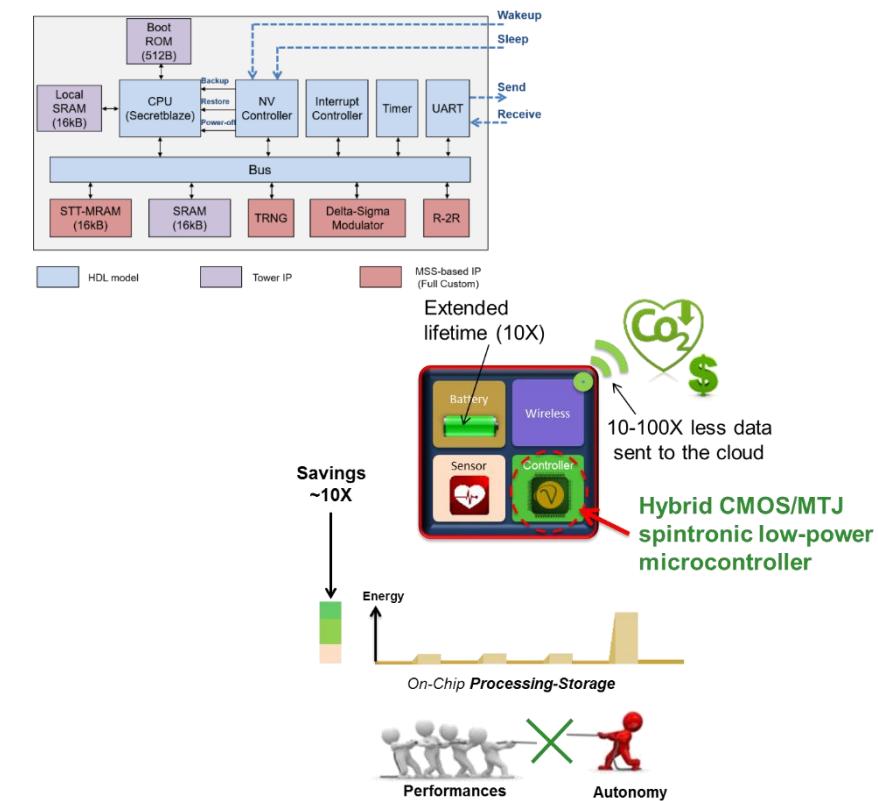
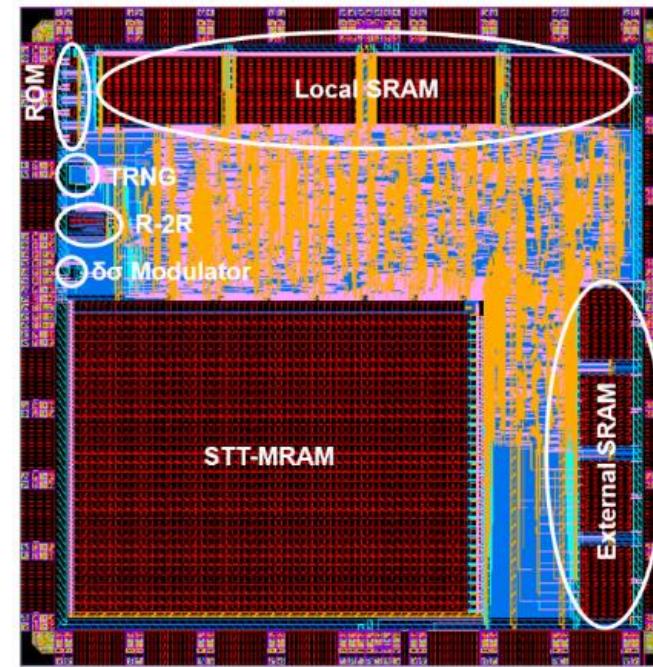
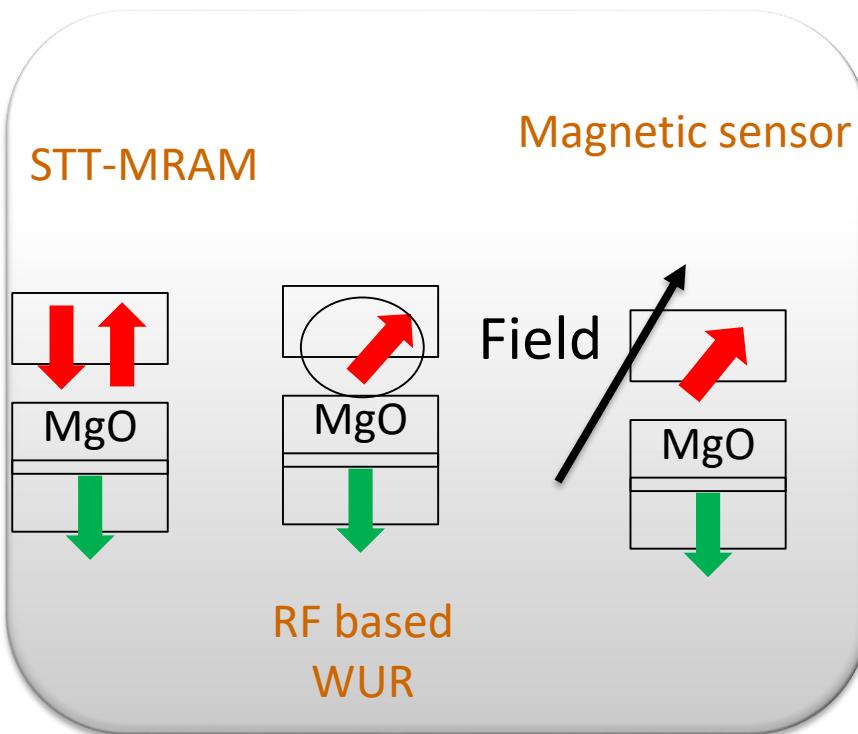
Energy harvesting
Temperature gradient (*spin-Seebeck*)

Ambient electromagnetic radiations (*spin-diodes*)

An “all” spintronics plateform opportunity

GREAT

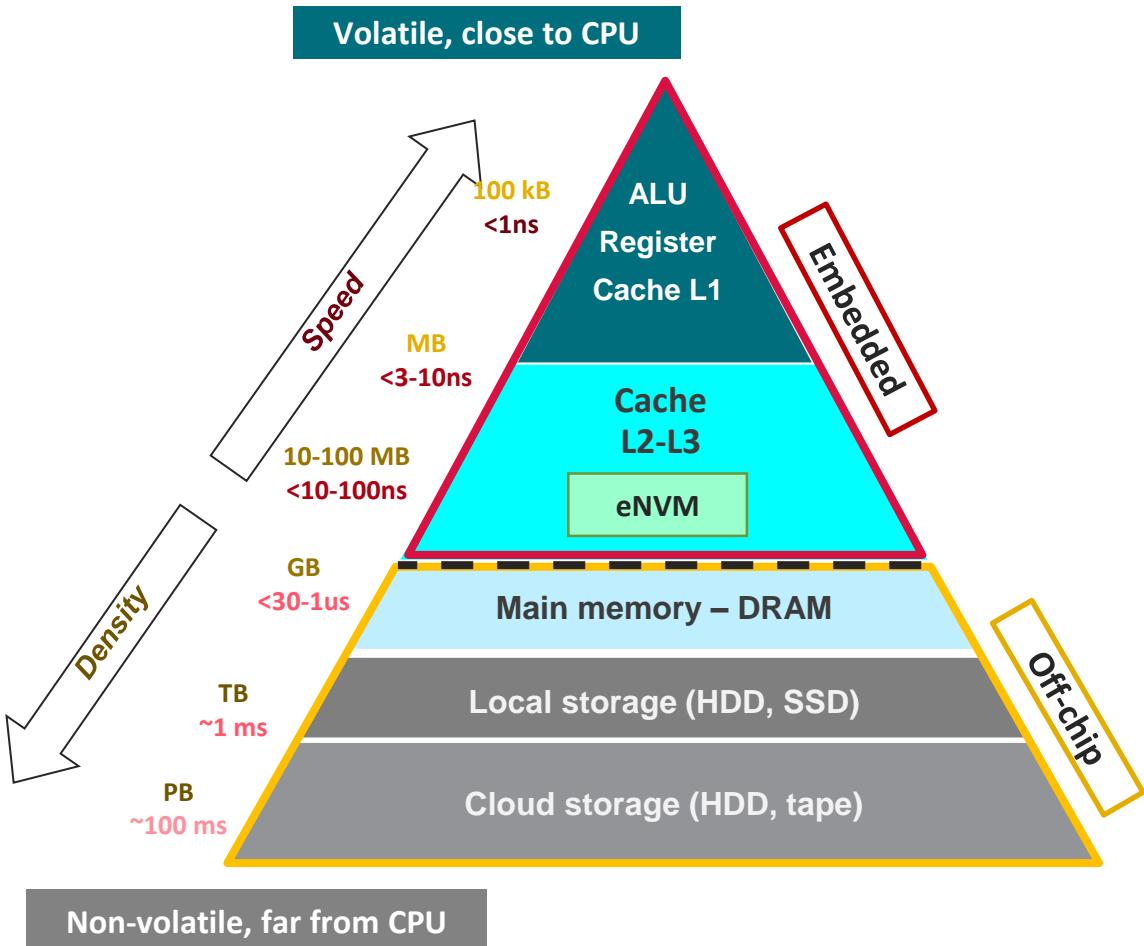
Three functionalities with same magnetic stack for Internet of Things allowing memory, sensing and RF on the same die



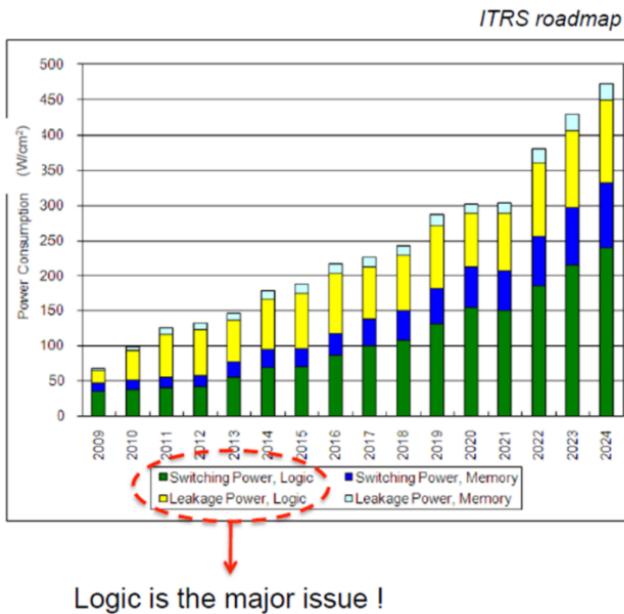
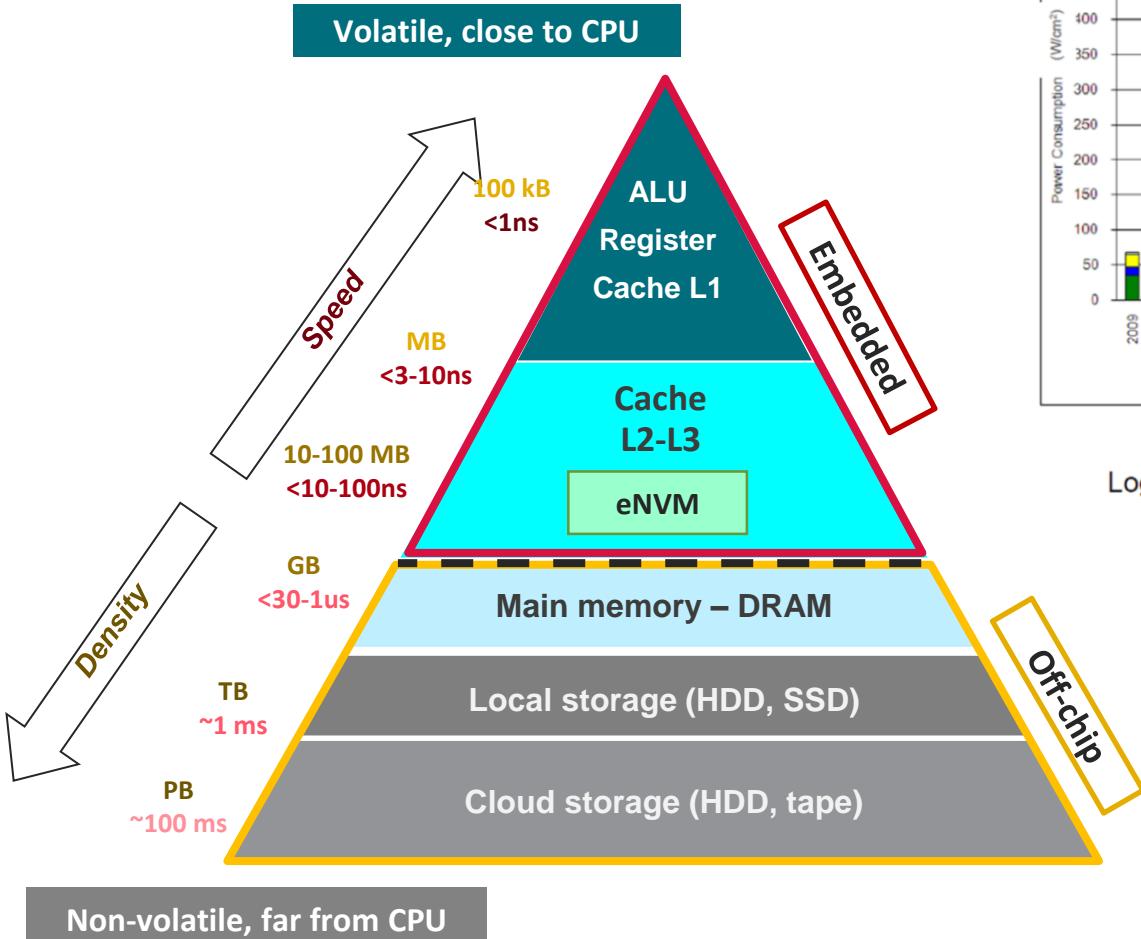
- Design of a 128kb memory array, compiler compatible
- First demonstration of a magnetic microcontroller embedding analog and digital functionalities

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Hiérarchie mémoire



Hiérarchie mémoire et impact du scaling



Conséquences de l'ultra scaling :

- Courant de fuite > courant écriture
- Augmentation coût de production
- Problèmes de fiabilité

→ **Introduction mémoires non-volatiles pour calcul faible puissance et on/off instantané**

Introduire les technologies NVM dans le cache

Augmentation la taille du cache

→ Réduire la dépendance DRAM

Revisite de l'architecture système

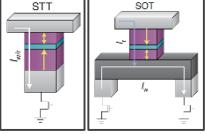
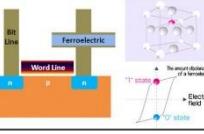
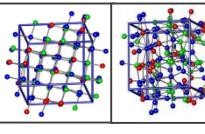
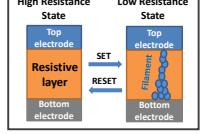
→ Gain de vitesse, puissance, efficacité

→ Développement de nouveaux concepts de calcul

Les technologies mémoires non volatiles

Introduire les technologies NVM dans le cache
= être compétitif avec la SRAM:

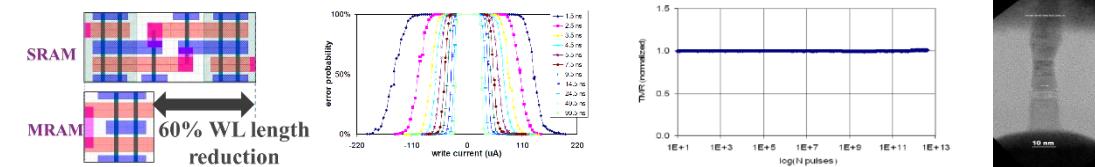
$\sim 1\text{ns}$, 10^{16} cycles, fJ

	Electroniques	Ioniques			
Mémoire CMOS (volatile)					
SRAM	MRAM	FeRAM Fe-FET	PC-RAM	RRAM	
V_{DD}	<1.1V	<1.1V	2V	3-5V	1.5-3.6V
Surface	1	0.4-1	0.4-1	0.4	0.4
Rapidité	ns	ns	20ns	100ns	100ns
Energie/bit	fJ	<pJ	10fJ	10pJ	10pJ
Endurance	>10¹⁶	10¹⁴⁻¹⁶	10¹²	10⁸	10⁶
Hiérarchie mémoire	Registre Cache	Cache eFLash	eFlash Autonome	eFlash Autonome	eFlash Autonome
Calcul IMC	ANN, Boolean, Learning	ANN, Boolean, Stochastic	ANN	ANN	ANN

Les mémoires **magnétorésistives** et **ferroélectriques** mieux placées pour besoins de l'embarqué et du calcul

La MRAM a des atouts à faire valoir

- CMOS compatible ($V_{sw} < V_{dd}$, BEOL)
- Fast (ns) & Endurance ($>10^{12}$)
- Scalable & dense

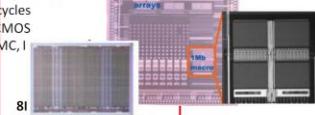
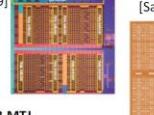
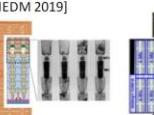


MRAM in production for embedded Flash replacement

STT-MRAM for Microcontrollers products

- 3 levels of masks vs. 15-20 masks for eFlash
- better endurance ($>10^{12}$ vs 10^5)
- faster write (40ns vs 100ms)
- reduced energy (400x reduction @ device)

Markets: Automotive (>50%); Smart Cards; Consumer

2014	2015 - 2016	2018 - 2019
 STT MRAM cycles CMOS IMC, I  8Gb 4ns access, 50nm diam. 125°C 10V / 400°C BEOL 50F2 90nm CMOS (limit. by T drive Eq. to 28 nm CMOS 67 F2 [Jan, TDK-Headway, VLSI2014])  Kbit for Gbit STT MRAM 130nm pitch; 0.017 μ m ² ; 28nm Program Energy 0.09pJ [Park, Qualcomm/AMAT, IEDM2015]	 1Mbit STT MRAM Read 16ns /Write 6ns @ 1.25V; 40nm LP [Lu, Qualcomm/TDK, IEDM2015]  4Mbit STT MRAM Read 3.3ns @ 1.25V 65nm CMOS [Noguchi, Toshiba, ISSCC 2016]	 7.2Mbit MTJ 1T-1MTJ 28nm FinFET 10 ⁶ endurance, 105°C, 200°C retention Embedded applications [Intel, IEDM 2018, ISSCC 2019]  1Gb embedded STT-MRAM 28nm FDSOI -40°C to 105°C, 10ys 105°C retention 10 ¹⁰ cycles Embedded and eDRAM applications [Samsung, IEDM 2019]  320Mb STT-MRAM 22nm -40°C to 150°C, 10ys 150°C, 10 ⁹ cycles Reflow and automotive uses [TSMC, IEDM 2019]

First usage case are on the market



Source: Huawei

Product 1 – Sony

- Sony's GNSS/GPS SoC (CXD5605) is based on a Samsung S4LP173 die manufactured on 28nm FDSOI that features 8Mb of eMRAM.
- Sony's CXD5605 chips are utilized in low-power Huawei Watch GT2. They were first introduced at the FDSOI Shanghai Forum in September 2019.



Source: Ambiq

Product 2 – Ambiq Micro

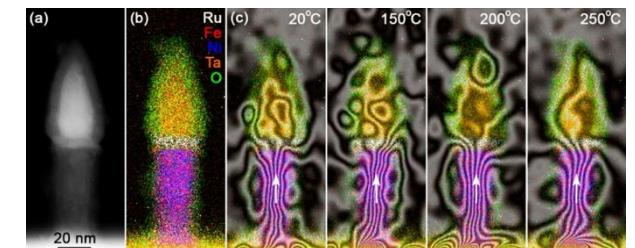
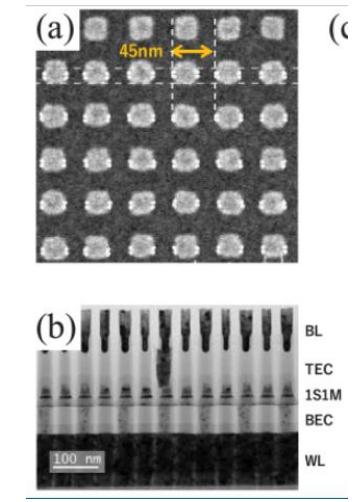
- In September 2020, Ambiq launched the 4th series of Apollo MCUs, which employ 16Mb eMRAM instead of eFlash. They are manufactured with TSMC's 22nm ULL process.
- Apollo 4 MCUs are based on Arm Cortex-M4, which runs up to 192 MHz while using 3 μ A/MHz (10 times lower than the industry average).
- The Apollo family of highly-integrated MCUs from Ambiq Micro are optimized for use in **wearable electronics, activity & fitness monitors, wireless sensors** and other **power-sensitive and battery-operated applications**.



Remaining limitations in STT-MRAM technology :

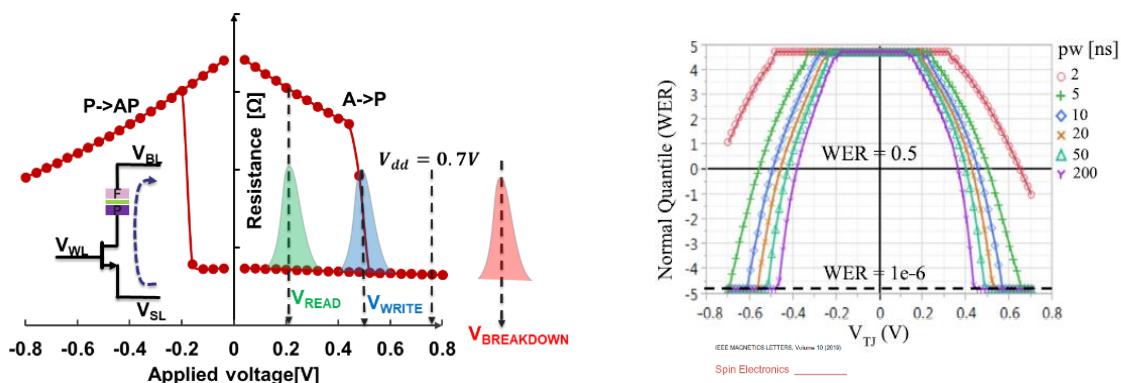
Hynix, <https://ieeexplore.ieee.org/document/10019549>

- Write speed : tradeoff speed/endurance
- High capacity: patterning at small feature size and narrow pitch
- Thermal stability at sub-20nm node and elevated temperatures



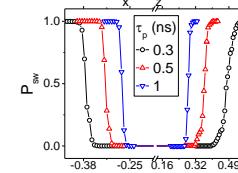
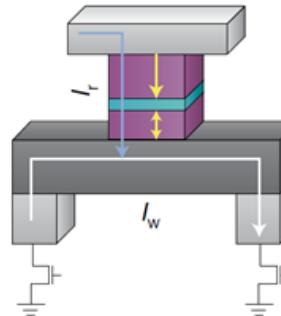
K. Watanabe *et al.*, *Nature com* (2018)
N.Perrissin *et al.*, *Nanoscale* 10, 12187-12195 (2018)

Vitesse écriture par STT :
Compromis écriture/endurance
 endurance vs. τ_{write} → Write latency > 10-15ns
Introduire MRAM in LLC:
 → Géométrie alternative, autre mécanisme écriture



Speed, advanced R&D

Spin-orbit torque (SOT)

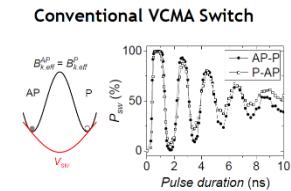
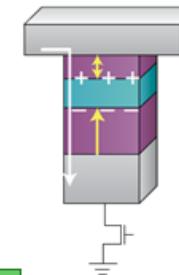


200 ps, 100 fJ, 3T

- Convertir charge en spin dans matériaux non FM
- Découplage écriture/lecture
 - "unlimited" endurance
 - No read disturb

Low power & fast, early R&D

Voltage control of anisotropy (VCMA)



500 ps, 10-100 fJ, 2T

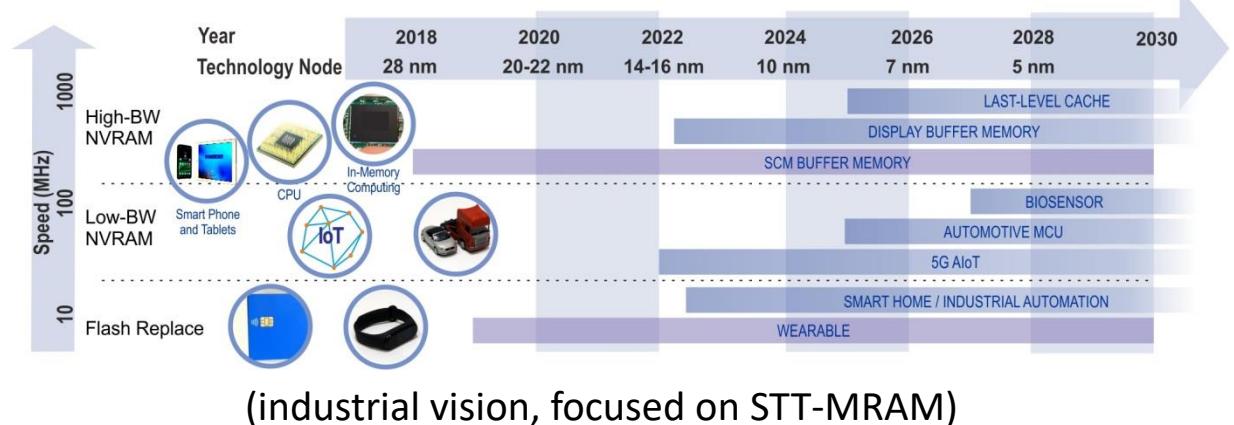
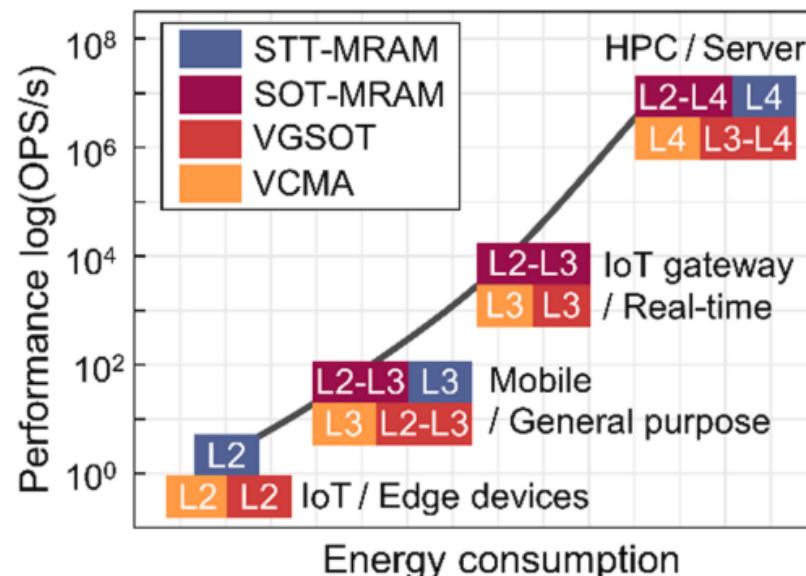
- Contrôle anisotropie par tension
- Exploite dynamique aimantation
- Ecriture unidirectionnel

Quelques projections des techno MRAM émergentes

Comparative table of potential embedded memory solutions at the macro level (5 nm node, 128 kbit) based on IMEC internal evaluations.

SPECS	EMBEDDED MEMORY OPTIONS										
	SRAM		STT		SOT			VCMA		VGSOT	
	HP (122)	HD (111)	HP (1.5 CPP)	HD (2 CPP)	5 T	HP (4 T)	HD (4 T)		2MTJ	4MTJ	
Bit-cell area (μm^2)	0.028	0.021	0.0108	0.0081	0.0162	0.0162	0.0135	0.0208	0.0122	0.009	
RD power/bit (nW)	18.7	7.28	7.44	6.20	25.5	29.0	32.9	3.16	3.16	2.96	
WR power/bit (nW)	25.7	9.85	29.2	24.4	31.4	34.7	35.3	59.2	47.5	46.5	
RD latency (ns)	~ 0.80	~ 1.50	~ 2.89	~ 3.75	~ 1.00	~ 1.00	~ 1.00	~ 10.0	~ 10.00	~ 10.00	
WR latency (ns)	~ 0.80	~ 1.50	~ 7.78	~ 20.00	~ 2.00	~ 1.40	~ 2.00	~ 1.00	~ 1.00	~ 1.00	
Endurance	10^{16}	10^{16}	10^7	10^9	10^{14}	10^{14}	10^{14}	10^{14}	10^{14}	10^{14}	
V_{DD} (V)	0.7	0.7	0.7	0.7	0.7	0.7	0.7	1.4	0.7	0.7	

Projection de champs d'applications possible

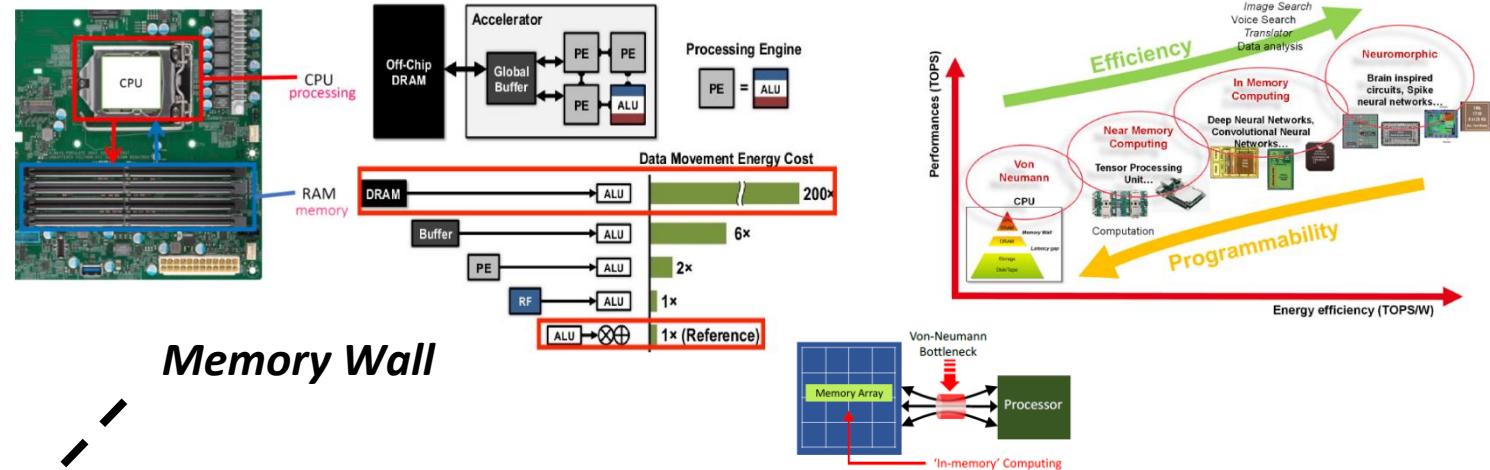
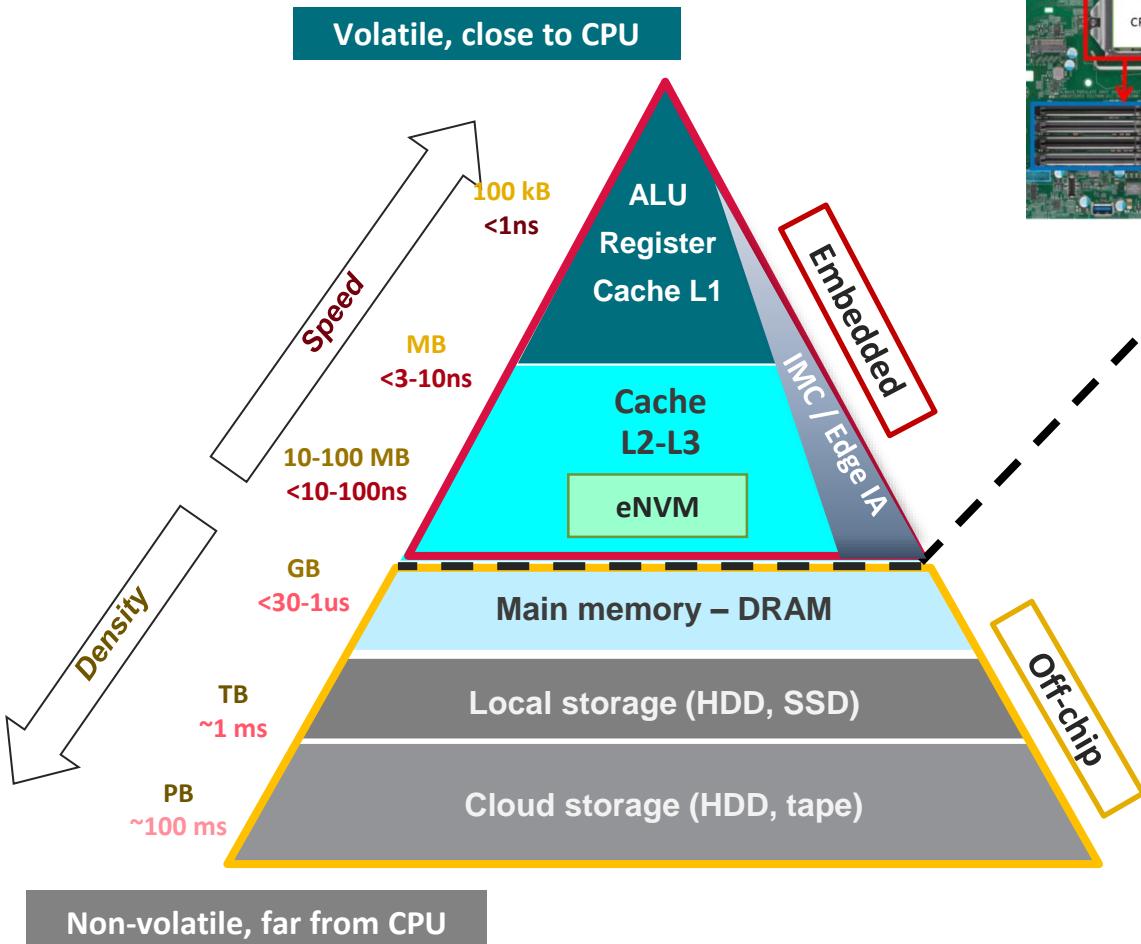


[1] V. Krizakova, KG et al., JMMM 562, p. 169692 (2022)

[2] H. Yang et. al, Two-dimensional materials prospects for non-volatile spintronic memories. Nature 606, 663–673 (2022)

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Memory wall: Vers In-Memory et Edge computing



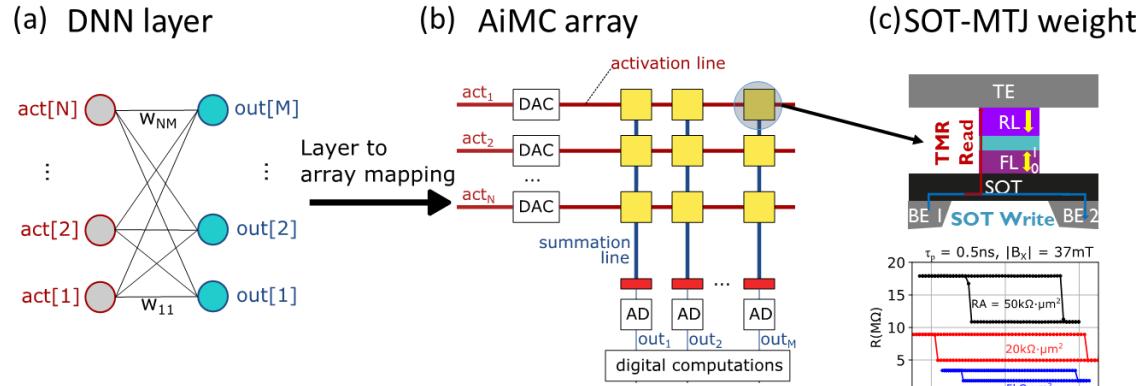
L'utilisation de données exploser, les contraintes énergétiques apparaissent
 ⇒ **Traitement local de l'information:
 In- & Near-Memory Computing**

- ✓ Perform logic operation inside memory
- ✓ Parallel, local data processing
- ✓ Low energy, programmable
- ✓ MRAM benefit: increased cache density

Au delà des mémoires: nouveaux paradigmes de calcul

In-memory computing

- Analog-iMC: DNN/SNN inference
Sort and Recognition (image, speech...)
- High Resistance is key → exploit third terminal → SOT



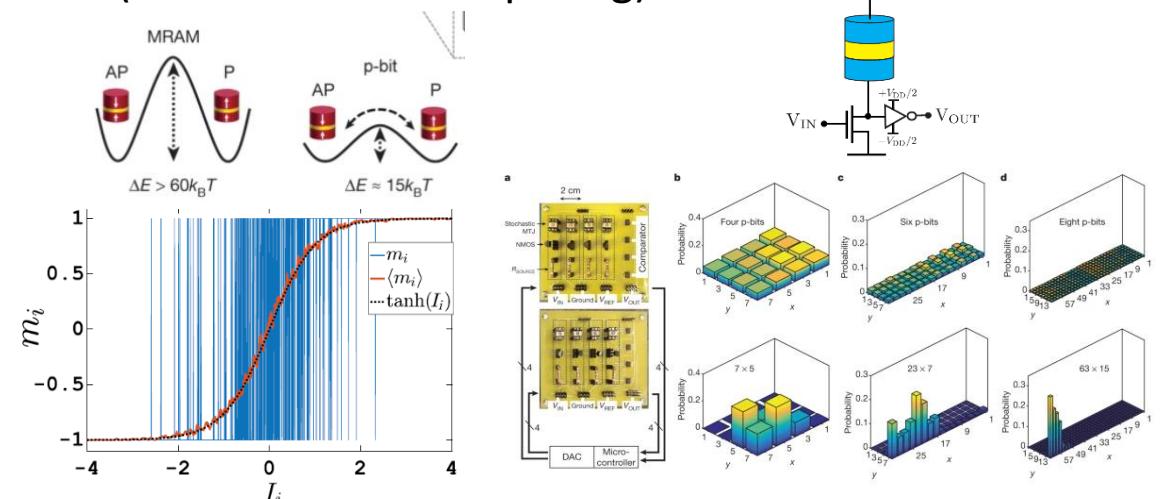
J. Doevenspeck, et al, VLSI 2020, JFS4.1 (2020), S. Jung, et al. A crossbar array of magnetoresistive Nature 601, 211–216 (2022)

Assess MRAM for emerging computing

- Low variability cell-to-cell
- Tunable properties: retention, resistance
- Speed

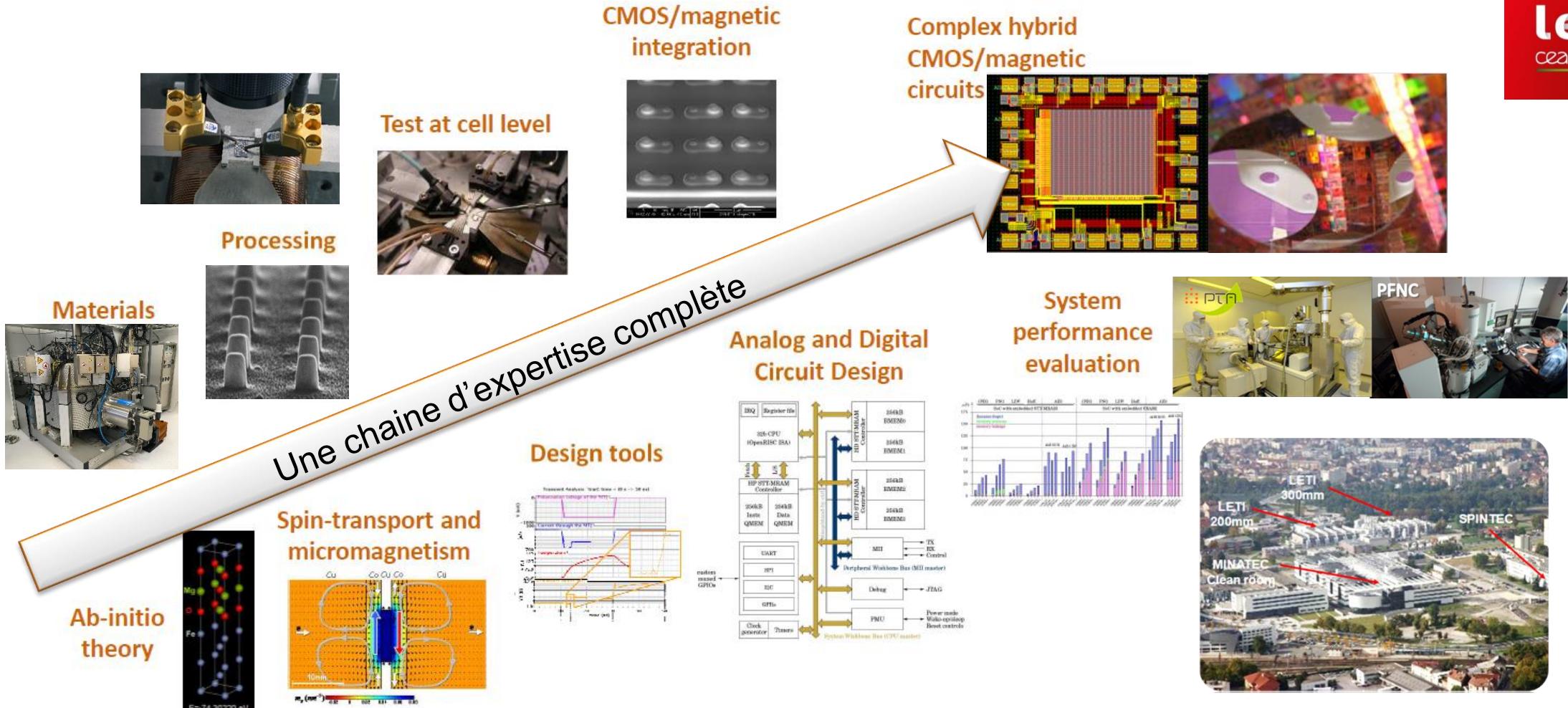
Stochastic /probabilistic computing

- Ising, Bayesian, pBit Factorization, full adder... functionalities (Quantum-like computing)



W. Borders et. al, Nature v573, pages390–393 (2019), Fukami et. al, NatureCom (2020)
Grollier, J., Querlioz, D., Camsari, K.Y. et al. Neuromorphic spintronics. Nat Electron 3, 360–370 (2020)

SPINTEC : Aller vers des démonstrations de concepts



21A1 + 2A2



9 chercheurs, 10

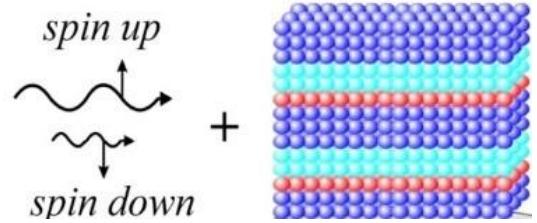


1 Prof + 2 MdC



2 Profs

A propos de SPINTEC : nos missions



Explore the frontiers of spintronics

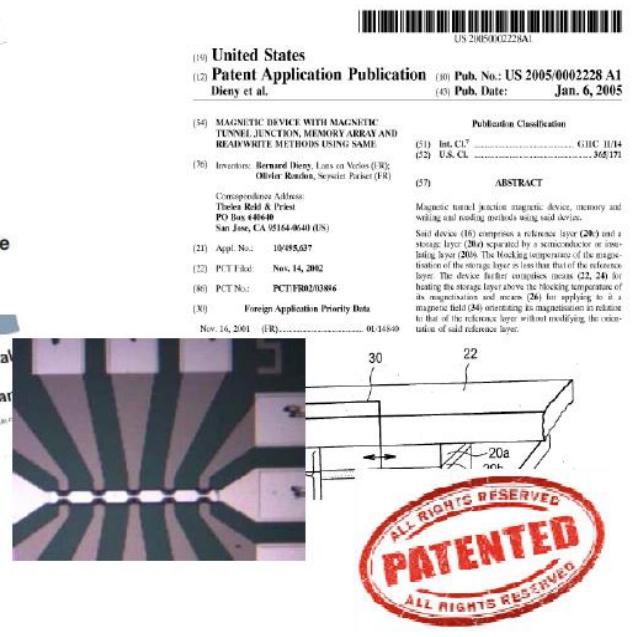
Invent new devices paradigms

Transfer technology to partners

Basic research



Applied Research



Valorization/exploitation



Magnetic field sensors and MRAM



Design of hybrid CMOS/magnetic circuits



Electrical probers for magnetic memories



Spin-Orbit-Torque memories

Projet PEPR : EMCOM (mémoires émergentes pour le calcul embarqué)



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DEFI

Calcul embarqué performant et économique en énergie

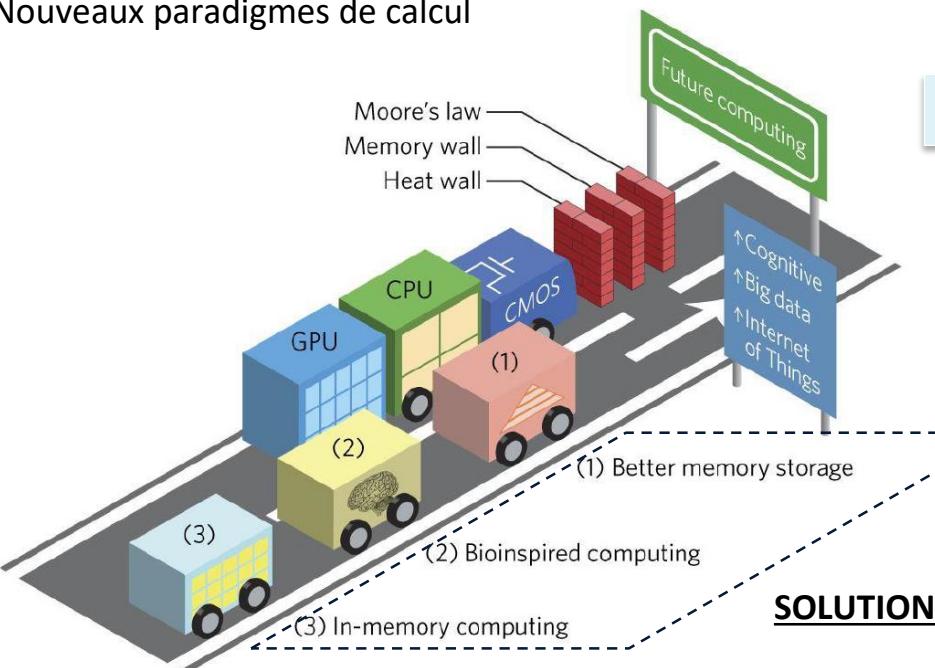
VERROUS

Moore's law, Memory wall, Heat wall

Vitesse d'écriture, très faible énergie, endurance

Architectures innovantes

Nouveaux paradigmes de calcul



(figure adaptée de Yole Development)

(1)

VG-SOT (WP2)
rapide, endurante,
multi-niveau

SPINTEC
LETI, C2N, UMPHY, IJL

FESO (WP3)
ultra faible
énergie

UMPHy
SPINTEC, LETI, C2N

Optique (WP4)
ultrarapide,
faible énergie

IJL
SPINTEC, LTM, C2N

Neuromorphique (WP5/6)
nouveaux paradigmes
de calcul

(2)

(3)

Benchmark, spécifications, architectures (WP1)



Vers une filière nationale MRAM / calcul embarqué

Matériaux (WP2-WP5)



Nanofabrication (WP2-WP5)



Caractérisation avancée (WP2-WP5)



Architectures (WP1)



CONCLUSIONS

- La STT-MRAM constitue la 2nd application majeur de la spintronics après les capteurs de champs magnétique (particulièrement pour HDD).
 - STT-MRAM est en phase de production en volume (Samsung, TSMC, Global Foundries, INTEL).
 - Marque l'acceptation de cette technologie CMOS/magnétique par l'industrie microélectronique
 - Première application: Remplacement de Flash embarquée
 - En développement: Last level Cache and memory persistantes (empreinte cellule < SRAM + non-volatile). SOT-MRAM et VCMA semblent mieux adresser ce sujet
 - Les propriétés MRAM peuvent adaptées aux specs des applications (résistance, rétention...)
- D'autres applications de la MRAM sont attendues dans le domaine de AI, In-memory computing, ultralow power electronics, IoT, High Performance Computing (HPC), cryoelectronics... mais des progrès matériaux / concept / architectures sont nécessaires → PEPR EMCOM



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Merci pour votre attention!

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